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apparatus; and

exposing another layer of said substrate by using said second exposure apparatus.

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3. (Amended) The exposure method according to Claim 2, further comprising:

adjusting an image forming characteristic of the second exposure apparatus in
consideration of a stored image distortion correction capability of said first exposure
apparatus.

6. (Amended) An exposure method of transferring a pattern of a second mask onto a
substrate using a second exposure apparatus after transferring a pattern of a first mask onto
said substrate using a first exposure apparatus, the method comprising:

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adjusting an image forming characteristic of said second exposure apparatus, in
consideration of an image distortion that can not be sufficiently corrected by said first
exposure apparatus; and

exposing said substrate to transfer the pattern of said second mask by using said second
exposure apparatus. C

7. (Amended) An exposure method of transferring a pattern of a first mask onto a
substrate using a first exposure apparatus before transferring a pattern of a second mask onto
said substrate using a second exposure apparatus, the method comprising:

adjusting an image forming characteristic of said first exposure apparatus, in
consideration of an image distortion that can not be sufficiently corrected by said second
exposure apparatus; and

exposing said substrate to transfer the pattern of said first mask by using said first
exposure apparatus.

8. (Amended) The exposure method according to Claim 7, wherein

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said second exposure apparatus is a scanning type exposure apparatus which moves said mask and said substrate synchronously during exposure, and

said image forming characteristic of said first exposure apparatus is adjusted so as to reduce an axially symmetrical image distortion component that can not be sufficiently corrected by said scanning type exposure apparatus.

9. (Amended) The exposure method according to Claim 7, wherein

said second exposure apparatus is a stationary type exposure apparatus in which said mask and said substrate are almost stationary during exposure, and

said image forming characteristic of said first exposure apparatus is adjusted so as to reduce an image distortion including a rectangular component and parallelogrammatic component that can not be sufficiently corrected by said stationary type exposure apparatus.

10. (Amended) An exposure method of transferring a pattern of a first mask onto a substrate using a first exposure apparatus, and of further transferring a pattern of a second mask onto said substrate using a second exposure apparatus, said method comprising:

adjusting an image forming characteristic of said first exposure apparatus, in accordance with stored information on an image distortion correction capability of said second exposure apparatus; and

transferring said pattern of said first mask onto said substrate.

11. (Amended) The exposure method according to Claim 10, wherein said image forming characteristic of said first exposure apparatus is adjusted so as to reduce an image distortion that can not be sufficiently corrected by said second exposure apparatus.

12. (Amended) An exposure method of transferring a pattern of a first mask onto a substrate using a first exposure apparatus, and of further transferring a pattern of a second mask onto said substrate using a second exposure apparatus, said method comprising:

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adjusting an image forming characteristic of said first exposure apparatus so as to leave an image distortion that can be corrected by said second exposure apparatus; and
transferring said pattern of said first mask onto said substrate.

13. (Amended) The exposure method according to Claim 12, wherein
said second exposure apparatus is a scanning type exposure apparatus which moves said mask and said substrate synchronously during exposure, and
said image forming characteristic of said first exposure apparatus is adjusted so at least one of image distortion components of a rectangular component and a parallelogrammatic component that can be corrected by said scanning type exposure apparatus remains on said substrate.

14. (Amended) The exposure method according to Claim 12, wherein
said second exposure apparatus is a stationary type exposure apparatus in which said mask and said substrate are almost stationary during exposure, and
said image forming characteristic of said first exposure apparatus is adjusted so at least one of image distortion components of a trapezoidal component and an axially symmetrical component that can be corrected by said stationary type exposure apparatus remains on said substrate.

15. (Amended) An exposure method of forming patterns of a plurality of layers on a substrate using a plurality of exposure apparatus, comprising:

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transferring a pattern of a first mask onto said substrate using a first exposure apparatus;

adjusting an image forming characteristic of a second exposure apparatus, in accordance with stored information about image distortion correction capability of said first exposure apparatus; and

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further transferring a pattern of a second mask onto said substrate using said second exposure apparatus after transferring the pattern of said first mask by said first exposure apparatus and adjusting said image forming characteristics of said second exposure apparatus.

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18. (Amended) The exposure method according to Claim 15, wherein transferring a pattern of a first mask is performed in a manner that said pattern of said first mask is transferred with a correction of an image distortion component that can not be sufficiently corrected by said second exposure apparatus.

22. (Amended) The exposure method according to Claim 19, wherein said one exposure apparatus of said first and second exposure apparatus corrects an image distortion component which can be corrected by said other exposure apparatus, and

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said one exposure apparatus of said first and second exposure apparatus corrects an image distortion component which is difficult or impossible to be corrected by said other exposure apparatus.

23. (Amended) The exposure method according to Claim 22, wherein said stationary type exposure apparatus corrects

at least one image distortion component of a rectangular component and parallelogrammatic component, and corrects

at least one image distortion component of a trapezoidal component and an axially symmetrical image distortion component

REMARKS

Favorable reconsideration of this application as presently amended and in light of the following discussion is respectfully requested.